

Substitute Form PTO-1449

U.S. Department of Commerce
Patent and Trademark OfficeAttorney's Docket No.
14414-019001Application No.
10/762,030**Information Disclosure Statement
by Applicant**

(Use several sheets if necessary)

Applicant
Raluca Dinu et al.Filing Date
January 21, 2004

Group Art Unit

2828

37 CFR §1.98(b))

U.S. Patent Documents

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date if Appropriate
TA	AA	5,120,339	06/09/92	Markovich et al.	—	—	
	AB	5,198,513	03/30/93	Clement et al.	—	—	
	AC	5,219,788	06/15/93	Abernathey et al.	—	—	
	AD	5,223,356	06/29/93	Kumar et al.	—	—	
	AE	5,370,969	12/06/94	Vidusek	—	—	
	AF	5,433,895	07/18/95	Jeng et al.	—	—	
	AG	5,480,687	01/02/96	Heming et al.	—	—	
	AH	5,497,445	03/05/96	Imoto	—	—	
	AI	5,635,576	06/03/97	Foll et al.	—	—	
	AJ	5,714,304	02/03/98	Gibbons et al.	—	—	
	AK	5,776,374	07/07/98	Newsham et al.	—	—	
	AL	5,783,319	07/21/98	Reisfeld et al.	—	—	
	AM	5,811,507	09/22/98	Chan et al.	—	—	
	AN	5,861,976	01/19/99	Hockstra	—	—	
	AO	5,887,116	03/23/99	Grote	—	—	
	AP	6,002,828	12/14/99	Hult et al.	—	—	
	AQ	6,019,906	02/01/00	Jang et al.	—	—	
	AR	6,031,945	02/29/00	You et al.	—	—	
	AS	6,060,170	05/09/00	Burgoyne, Jr.	—	—	
	AT	6,117,967	09/12/00	Fuller, et al.	—	—	
	AU	6,126,867	10/03/00	Kanitz et al.	—	—	
	AV	6,229,949	05/08/01	Ido et al.	—	—	
	AW	6,294,573	09/25/01	Curtin et al.	—	—	
	AX	6,303,730	10/16/01	Fries et al.	—	—	
	AY	6,306,563	10/23/01	Xu et al.	—	—	
	AZ	6,323,361	11/27/01	Wu et al.	—	—	
	AAA	6,335,149	01/01/02	Xu et al.	—	—	
TA	ABB	6,419,989	07/16/02	Betz et al.	—	—	

Examiner Signature

Date Considered

9/04/04

EXAMINER: Initials citation considered. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.



Substitute Form PTO-1449 (Modified)	U.S. Department of Commerce Patent and Trademark Office	Attorney's Docket No. 14414-019001	Application No. 10/762,030
		Applicant Raluca Dinu et al.	
		Filing Date January 21, 2004	Group Art Unit 2826

(37 CFR §1.98(b))

U.S. Patent Documents

Examiner Initial	Desig. ID	Document Number	Publication Date	Patentee	Class	Subclass	Filing Date If Appropriate
JA	ACC	6,466,707	10/15/02	Dawes, et al.	—	—	
I	ADD	6,473,551	10/29/02	Norwood, et al.	—	—	
	AEE	10/264,461	N/A	Dinu et al.	—	—	
JA	AFF	10/301,978	N/A	Huang et al.	—	—	

Foreign Patent Documents or Published Foreign Patent Applications (ABSTRACT)

Examiner Initial	Desig. ID	Document Number	Publication Date	Country or Patent Office	Class	Subclass	Translation	
							Yes	No
JA	AGG	961139	01/12/99	EP	—	—	X	
I	AHH	10049443	02/20/98	JP	—	—	X	
	AII	2001255426	09/21/01	JP	—	—	X	
	AJJ	09258151	10/03/97	JP	—	—	X	
	AKK	10232323	09/02/98	JP	—	—	X	
JA	ALL	04238305	08/26/92	JP	—	—	X	

Other Documents (include Author, Title, Date, and Place of Publication)

Examiner Initial	Desig. ID	Document
JA	AMM	Bailey et al., "Step and flash imprint lithography: Template surface treatment and defect analysis," <u>J. Vac. Sci. Technol. B</u> , 2000, 18(6):3572-3577
I	ANN	Chen et al., "Thermosetting Polyurethanes with Stable and Large Second-Order Optical Nonlinearity," <u>Macromolecules</u> , 1992, 25:4032-4035
	AOO	Grote et al., "Effect of conductivity and dielectric constant on the modulation voltage for optoelectronic devices based on nonlinear optical polymers," <u>Opt. Eng.</u> , 2001, 40(11):2464-2473
	APP	Ma et al., "A Novel Class of High-Performance Perfluorocyclobutane-Containing Polymers for Second-Order Nonlinear Optics," <u>Chem. Mater.</u> , 2000, 12:1187-1189
	AQQ	Ma et al., "Highly Efficient and Thermally Stable Nonlinear Optical Dendrimer for Electrooptics," <u>J. Am. Chem. Soc.</u> , 2001, 123:986-987
	ARR	Mao et al., "Progress toward Device-Quality Second-Order Nonlinear Optical Materials. 1. Influence of Composition and Processing Conditions on Nonlinearity, Temporal Stability, and Optical Loss," <u>Chem. Mater.</u> , 1998, 10:146-155
	ASS	Oh et al., "Electro-optic polymer modulators for 1.55 μm wavelength using phenyltetraene bridged chromophore in polycarbonate," <u>Appl. Phys. Lett.</u> , 2000, 76(24):3525-3527
JA	ATT	Resnick et al., "Release Layers for Contact and Imprint Lithography," <u>Semicon. Int.</u> , June 2002, online version, 7 pgs.

Examiner Signature 	Date Considered 9/3/04
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